

### AMENDMENTS TO THE SPECIFICATION

#### In the Abstract

Please amend the current abstract as follows (a clean version of the amended abstract is attached hereto as a separate sheet):

A polishing composition comprising 0.03 to 0.5% by weight of an organic acid or a salt thereof, an abrasive and water, wherein the abrasive has a surface potential of from -140 to 200 mV; a roll-off reducing agent comprising an inorganic compound having a property of controlling a surface potential of an abrasive in a polishing composition, wherein a surface potential of the abrasive in a standard polishing composition is controlled to -110 to 250 mV by the presence of the inorganic compound, wherein the standard polishing composition is prepared which comprises 20 parts by weight of an abrasive, the abrasive being high-purity alumina having  $\text{Al}_2\text{O}_3$  purity of 98.0% by weight or more composed of  $\alpha$ -type ~~eo-random~~ corundum crystal, 1 part by weight of citric acid, 78 parts by weight of water and 1 part by weight of an inorganic compound. The polishing composition or the roll-off reducing agent composition can be favorably used in polishing the substrate for precision parts.

In the Specification

The paragraph beginning on page 2, line 21, is being amended as follows:

[2] a roll-off reducing agent comprising an inorganic compound having a property of controlling a surface potential of an abrasive in a polishing composition, wherein a surface potential of the abrasive in a standard polishing composition is controlled to -110 to 250 mV by the presence of the inorganic compound, wherein the standard polishing composition is prepared which comprises 20 parts by weight of an abrasive, the abrasive being high-purity alumina having  $\text{Al}_2\text{O}_3$  purity of 98.0% by weight or more composed of  $\alpha$ -type ~~eo-random~~ corundum crystal, 1 part by weight of citric acid, 78 parts by weight of water and 1 part by weight of an inorganic compound;

The paragraph beginning on page 15, line 13, is being amended as follows:

As mentioned above, the roll-off reducing agent of the present invention comprises an inorganic compound having a property of controlling a surface potential of an abrasive in a polishing composition, wherein a surface potential of the abrasive in a standard polishing composition (hereinafter also referred to as a "specified surface potential B") is controlled to -110 to 250 mV in the presence of the inorganic compound, when the standard polishing composition comprising 20 parts by weight of an abrasive (high-purity alumina having  $\text{Al}_2\text{O}_3$  purity of 98.0% by weight, composed of  $\alpha$ -type ~~eo-random~~ corundum crystal), 1 part by weight of citric acid, 78 parts by weight of water and 1 part by weight of an inorganic compound is prepared. In the present invention, since the roll-off reducing agent is formulated in the polishing composition, there are exhibited some remarkable effects that the roll-off of the substrate can be

significantly reduced, so that a substrate capable of recording to an outer peripheral portion can be produced.

The paragraph beginning on page 17, line 3, is being amended as follows:

In the present invention, the standard polishing composition comprising 1% by weight of an inorganic compound is a polishing composition comprising 20 parts by weight of an abrasive (high-purity alumina having  $\text{Al}_2\text{O}_3$  purity of 98.0% by weight or more composed of  $\alpha$ -type ~~eo-random~~ corundum crystal), 1 part by weight of citric acid, 78 parts by weight of water and 1 part by weight of a roll-off reducing agent. Therefore, in the present invention, the surface potential is a surface potential of an abrasive of the polishing composition comprising citric acid.

The paragraph beginning on page 17, line 11, is being amended as follows:

As the high-purity alumina having  $\text{Al}_2\text{O}_3$  purity of 98.0% by weight or more composed of  $\alpha$ -type ~~eo-random~~ corundum crystal used as an abrasive in the standard polishing composition, the high-purity alumina containing 1.2% by weight or less of  $\text{SiO}_2$ , 0.2% by weight or less of  $\text{Fe}_2\text{O}_3$ , and 0.7% by weight or less of  $\text{Na}_2\text{O}$  as other components is preferable, and the alumina having a particle size of 0.6  $\mu\text{m}$  at 50% accumulative point is preferable. Concrete examples thereof include one commercially available from Fujimi Incorporated under the trade name of "WA#10000."